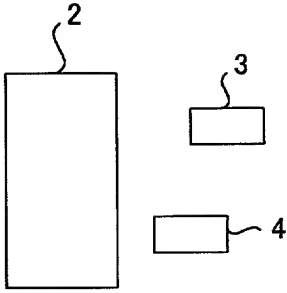
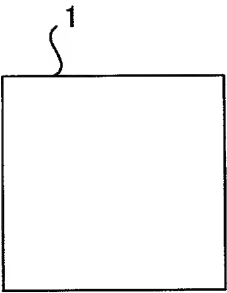


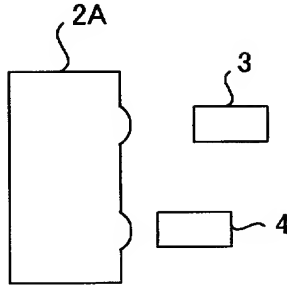
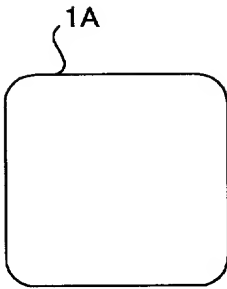
FIG. 1

OPTICAL PROXIMITY EFFECT

(1) EXPOSURE
PATTERN



(2) RETICLE
PATTERN



(3) WAFER
PATTERN

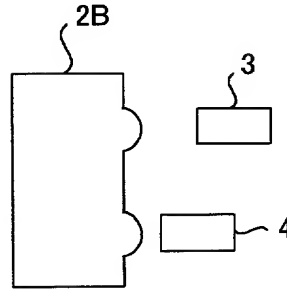
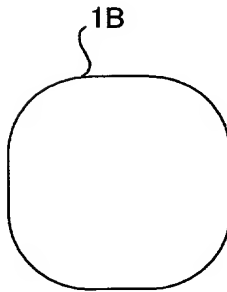
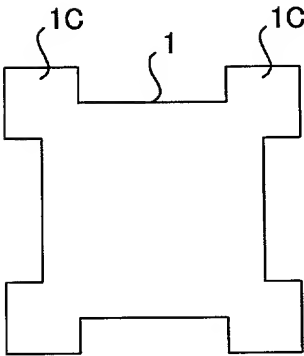


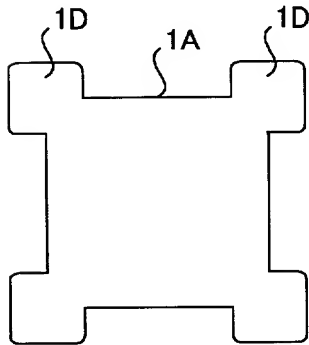
FIG. 2

OPTICAL PROXIMITY CORRECTION

(1) EXPOSURE
PATTERN



(2) RETICLE
PATTERN



(3) WAFER
PATTERN

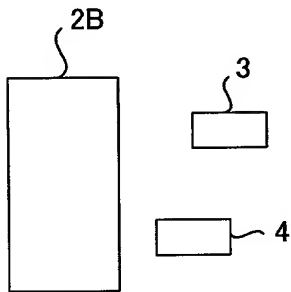
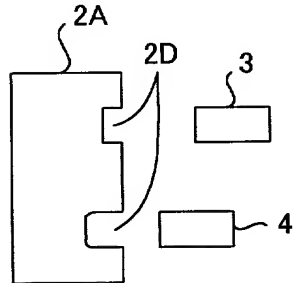
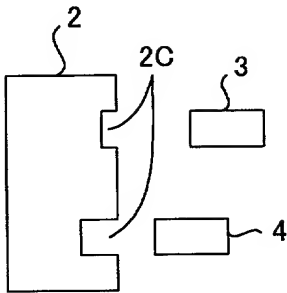
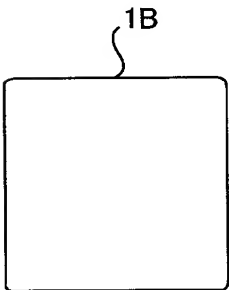
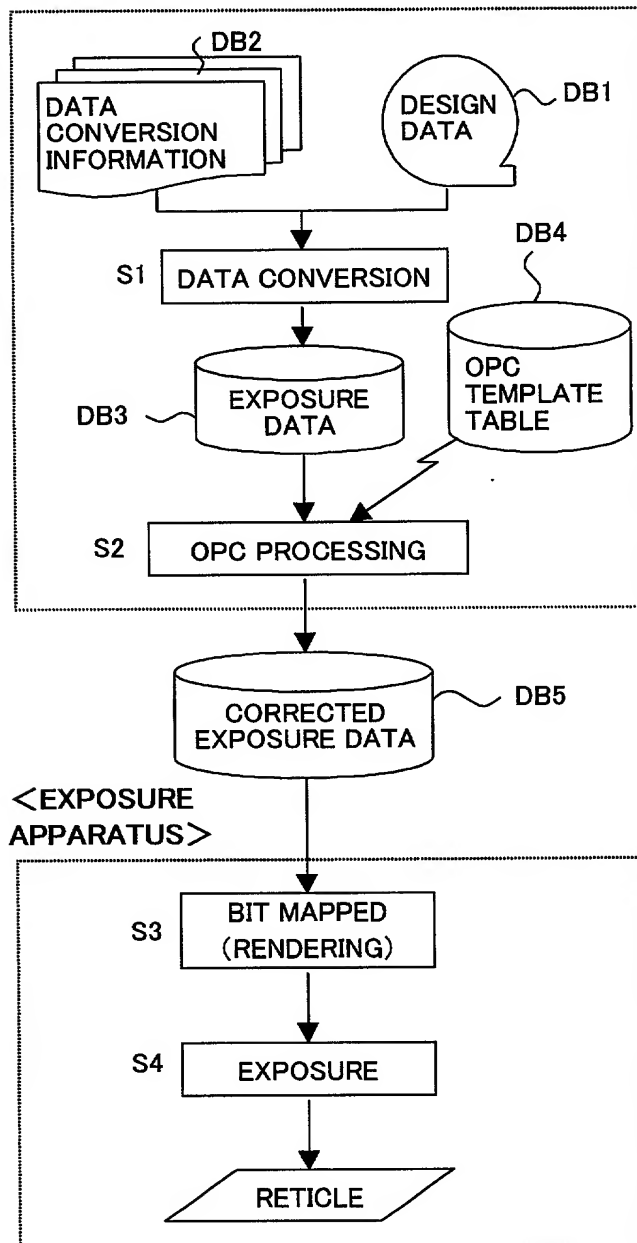


FIG. 3

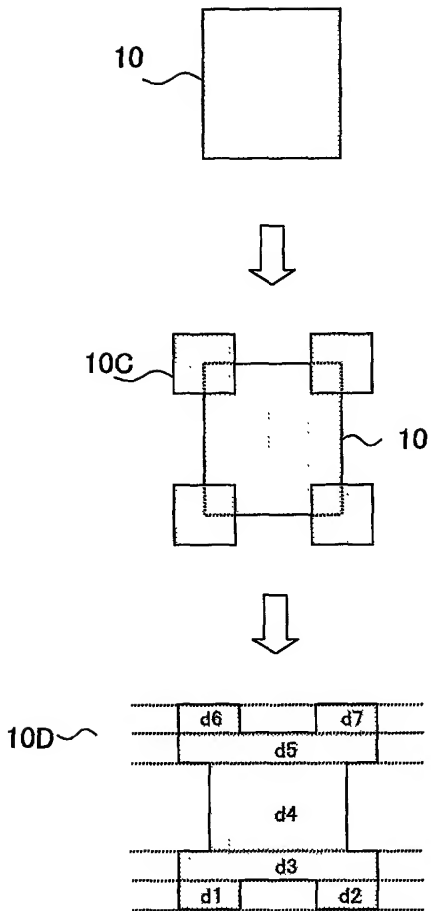
FIRST OPC PROCESSING

<EXPOSURE DATA PROCESSING APPARATUS>



FIRST OPC PROCESSING

FIG. 4A



EXPOSURE,
DEVELOPMENT

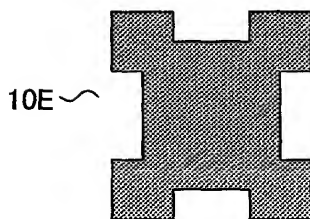
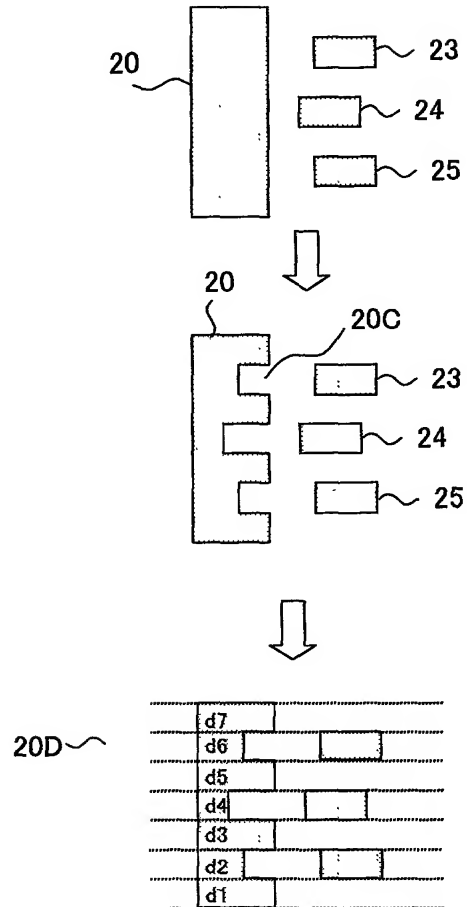
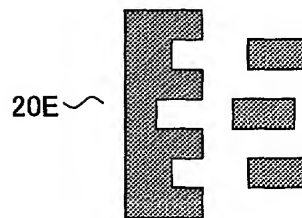


FIG. 4B



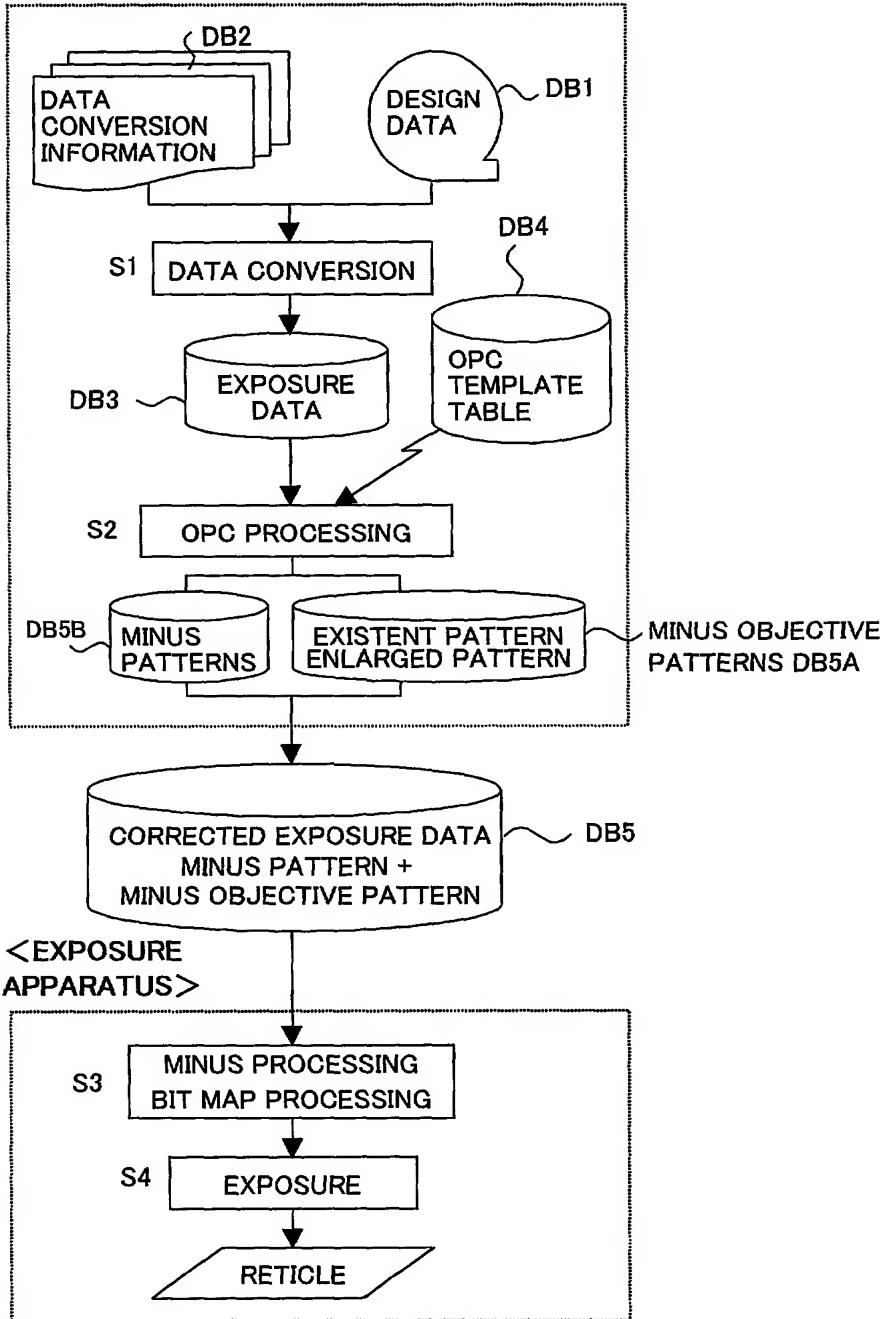
EXPOSURE,
DEVELOPMENT



[illegible]

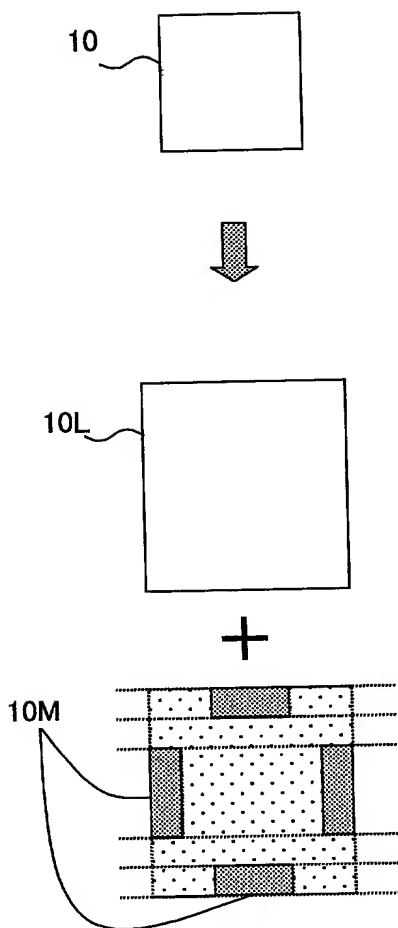
SECOND OPC PROCESSING

<EXPOSURE DATA PROCESSING APPARATUS>



SECOND OPC PROCESSING

FIG. 6A



EXPOSURE,
DEVELOPMENT

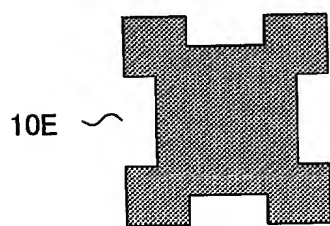
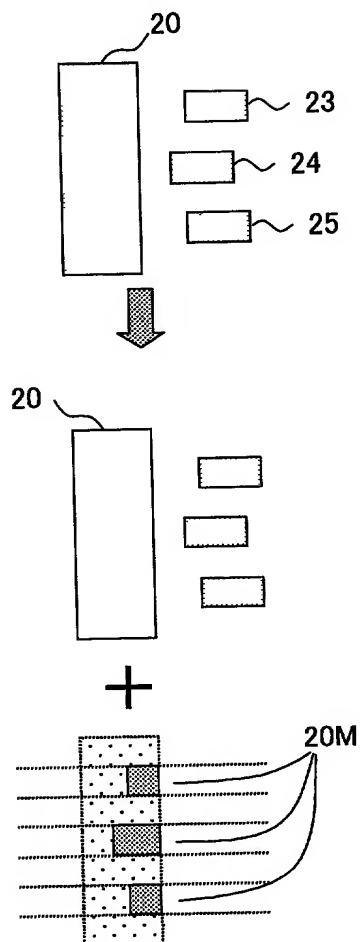


FIG. 6B



EXPOSURE,
DEVELOPMENT

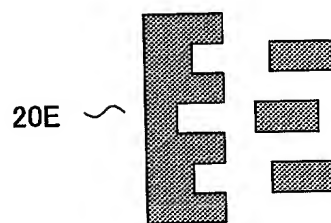


FIG. 7

OPC PROCESSING

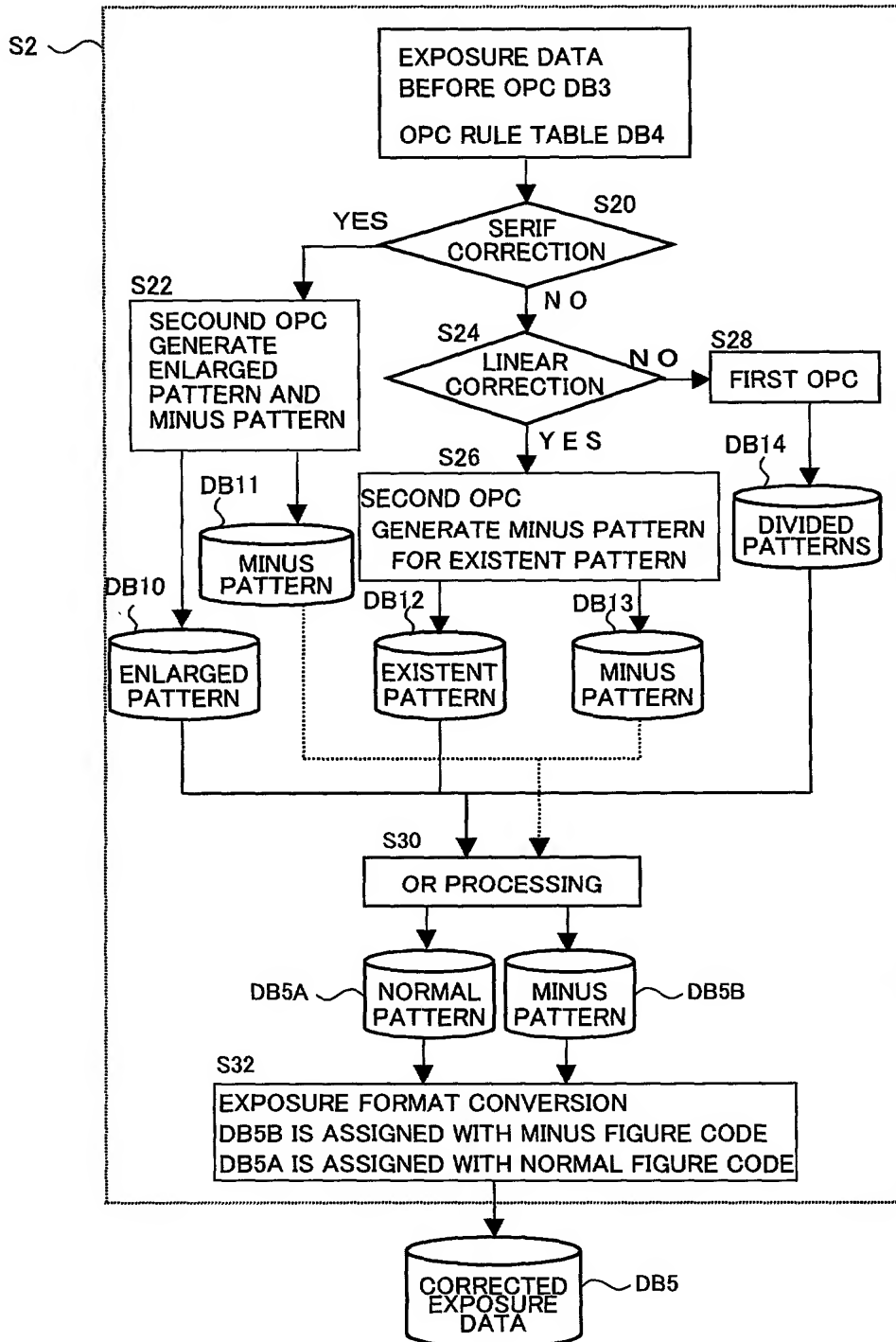


FIG. 8A

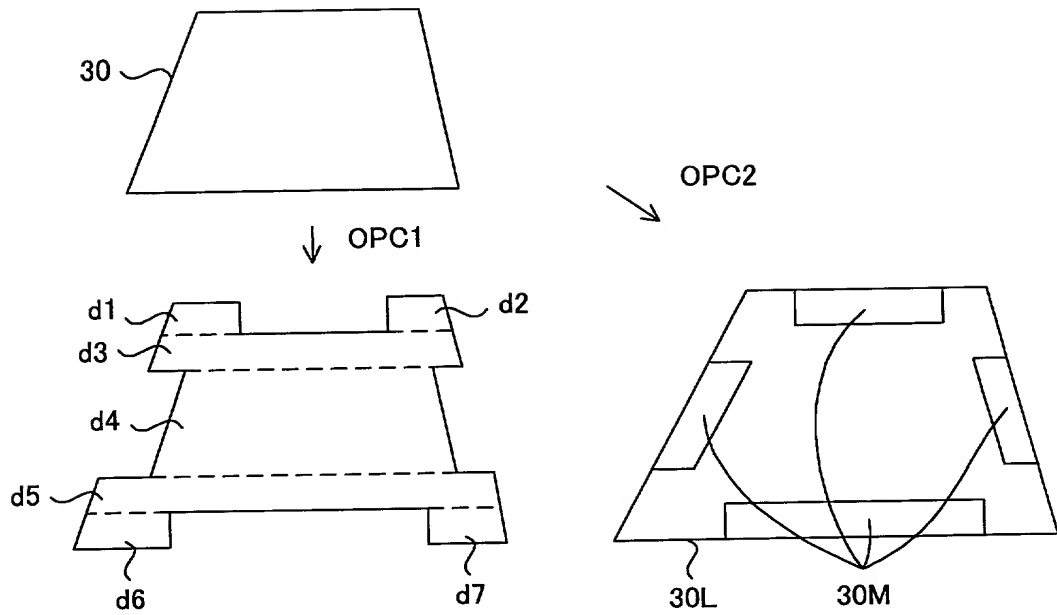


FIG. 8B

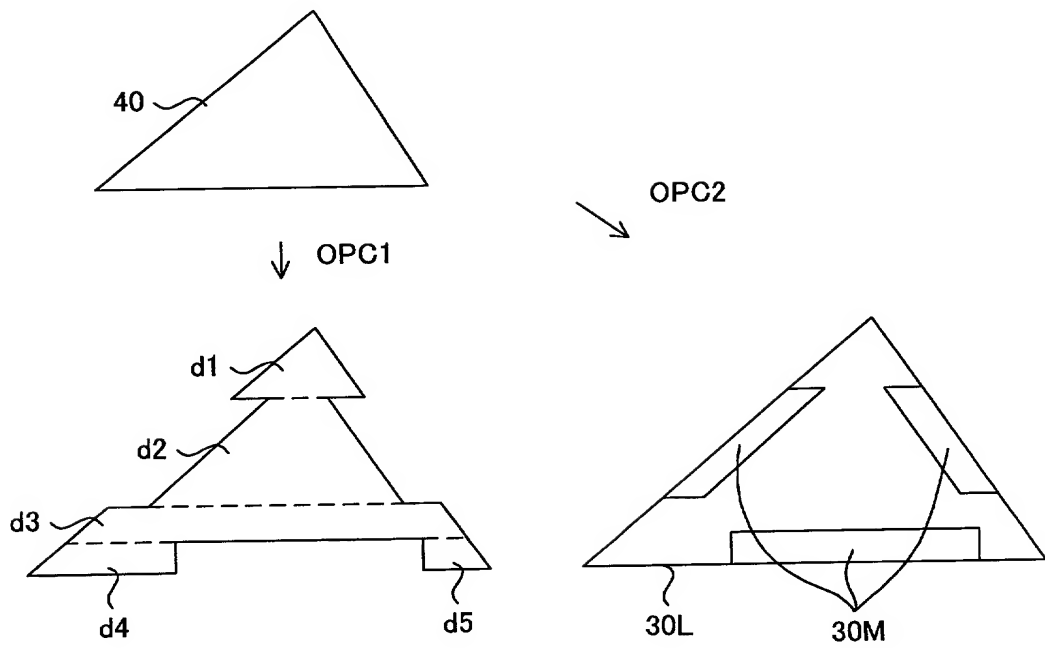


FIG. 9A

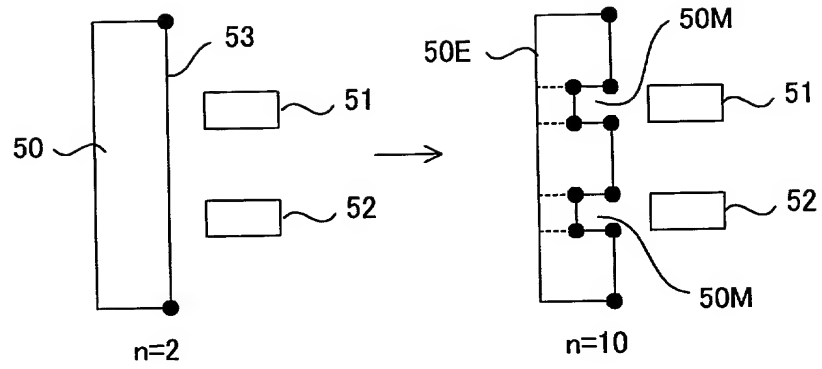


FIG. 9B

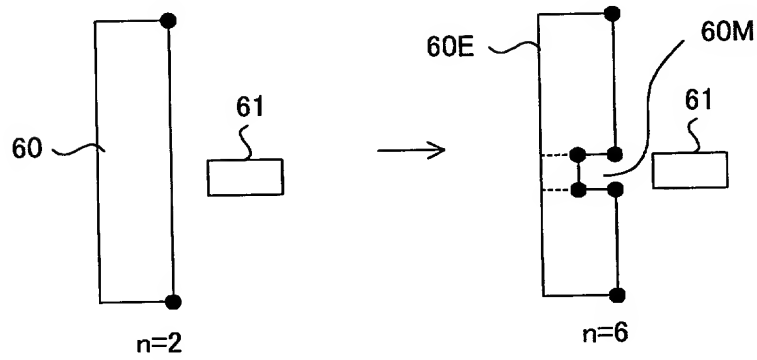


FIG. 9C

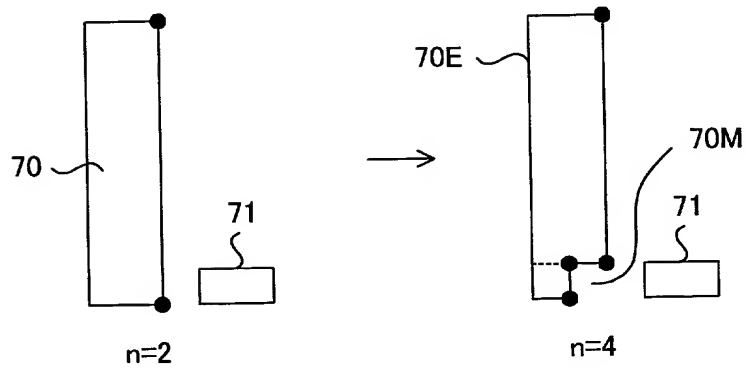


FIG. 10

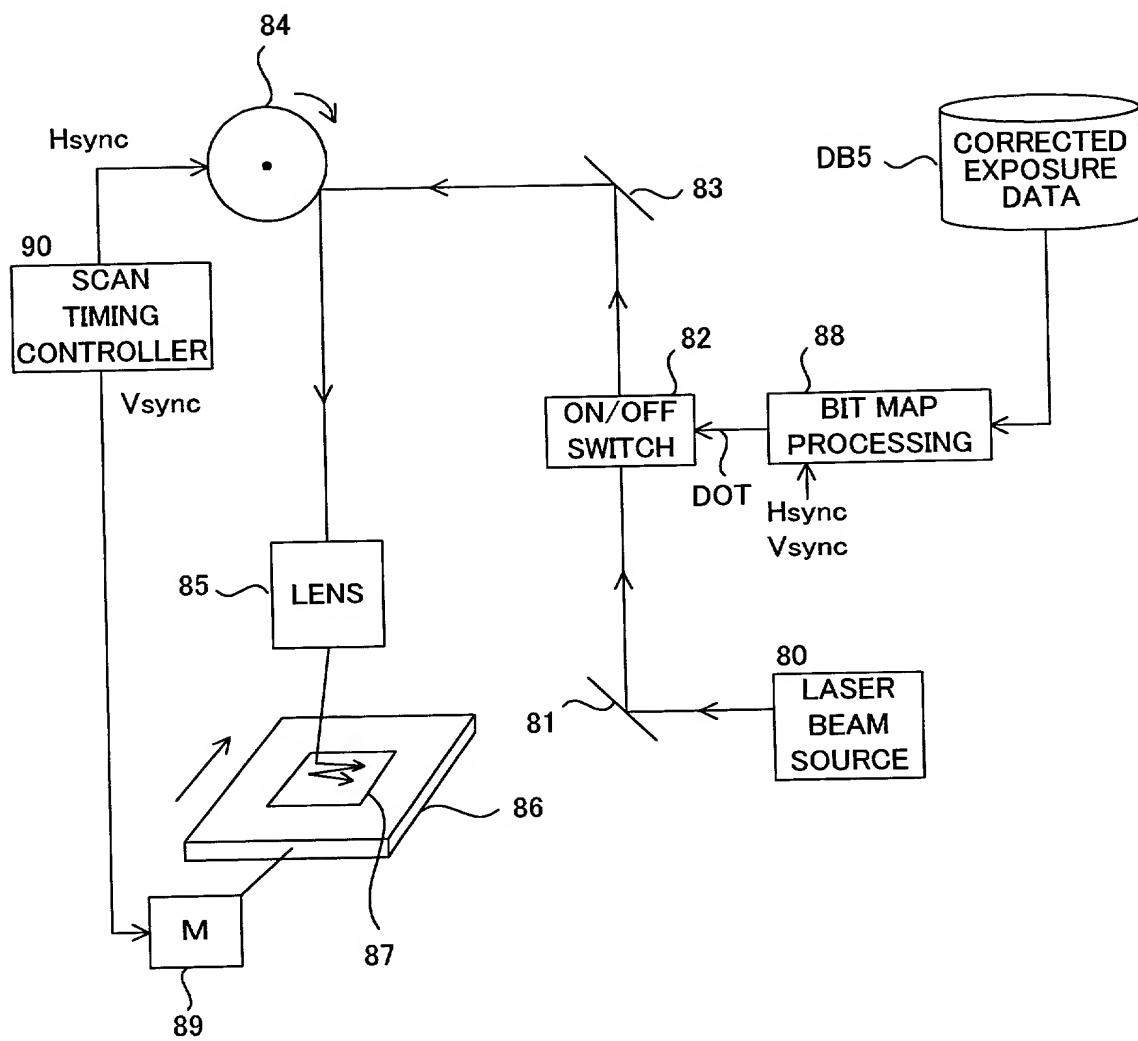


FIG. 11

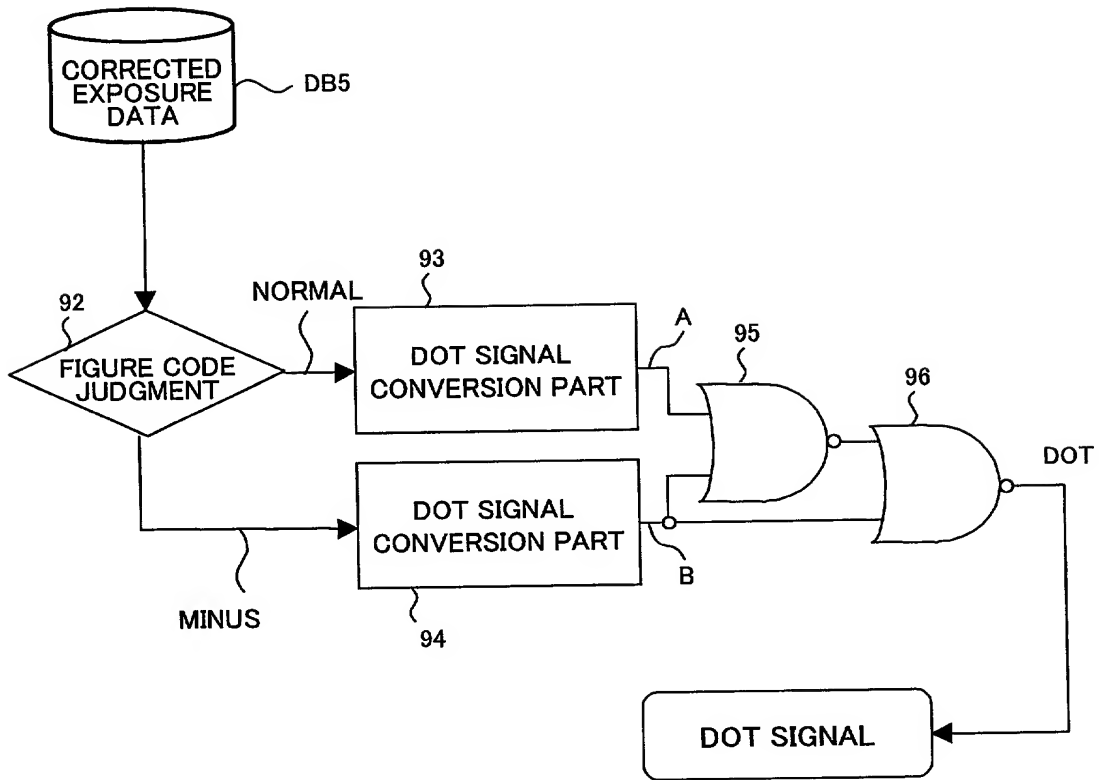


FIG. 12

A	B	DOT SIGNAL
0	0	0
0	1	0
1	0	1
1	1	0